

L Number	Hits	Search Text	DB	Time stamp
1	17446	(poly\$1silicon or (poly\$1crystalline adj silicon)) same (mask or hard\$1mask)	USPAT	2004/04/30 13:19
2	2808	((poly\$1silicon or (poly\$1crystalline adj silicon)) same (mask or hard\$1mask)) and (isotropic\$4)	USPAT	2004/04/30 08:51
3	15	((poly\$1silicon or (poly\$1crystalline adj silicon)) same (mask or hard\$1mask)) and (isotropic\$4)) and (ground\$1rule)	USPAT	2004/04/30 09:19
4	0	sub\$1minimum adj ground\$1rule	USPAT	2004/04/30 08:55
5	15	minimum adj ground\$1rule	USPAT	2004/04/30 08:55
6	513	((poly\$1silicon or (poly\$1crystalline adj silicon)) same (mask or hard\$1mask)) and (isotropic\$4)) and ((trim or trimmed or trimming or narrow or narrowing or under\$1cut or under\$1cutting) same (poly\$1silicon or (poly\$1crystalline adj silicon)))	USPAT	2004/04/30 09:35
7	235	((((poly\$1silicon or (poly\$1crystalline adj silicon)) same (mask or hard\$1mask)) and (isotropic\$4)) and ((trim or trimmed or trimming or narrow or narrowing or under\$1cut or under\$1cutting) same (poly\$1silicon or (poly\$1crystalline adj silicon)))) and (HF or hydro\$1fluoric)	USPAT	2004/04/30 09:22
8	224	(((((poly\$1silicon or (poly\$1crystalline adj silicon)) same (mask or hard\$1mask)) and (isotropic\$4)) and ((trim or trimmed or trimming or narrow or narrowing or under\$1cut or under\$1cutting) same (poly\$1silicon or (poly\$1crystalline adj silicon)))) and (HF or hydro\$1fluoric)) and @ay<=2001	USPAT	2004/04/30 09:22
9	120	((((poly\$1silicon or (poly\$1crystalline adj silicon)) same (mask or hard\$1mask)) and (isotropic\$4)) and ((trim or trimmed or trimming or narrow or narrowing or under\$1cut or under\$1cutting) same (poly\$1silicon or (poly\$1crystalline adj silicon)))) and ((HF or hydro\$1fluoric) with (poly\$1silicon or silicon))	USPAT	2004/04/30 09:23
10	13197	((poly\$1silicon or (poly\$1crystalline adj silicon)) same (mask or hard\$1mask)) and (resist or photo\$1resist or photo\$1sensitive)	USPAT	2004/04/30 09:31
11	2225	((poly\$1silicon or (poly\$1crystalline adj silicon)) same (mask or hard\$1mask)) and (resist or photo\$1resist or photo\$1sensitive)) and ((poly\$1silicon or (poly\$1crystalline adj silicon)) same (HF or hydro\$1fluoric or ammonium or "NH.sub.4 OH"))	USPAT	2004/04/30 09:33
12	970	((((poly\$1silicon or (poly\$1crystalline adj silicon)) same (mask or hard\$1mask)) and (resist or photo\$1resist or photo\$1sensitive)) and ((poly\$1silicon or (poly\$1crystalline adj silicon)) same (HF or hydro\$1fluoric or ammonium or "NH.sub.4 OH")) and ((mask or hard\$1mask) with (SiO or (silicon adj oxide) or (silicon adj dioxide) or SiO?sub.2)))	USPAT	2004/04/30 09:34

13	926	(((((poly\$1silicon or (poly\$1crystalline adj silicon)) same (mask or hard\$1mask)) and (resist or photo\$1resist or photo\$1sensitive)) and ((poly\$1silicon or (poly\$1crystalline adj silicon)) same (HF or hydro\$1fluoric or ammonium or "NH.sub.4 OH")))) and ((mask or hard\$1mask) with (SiO or (silicon adj oxide) or (silicon adj dioxide) or SiO?sub.2))) and @ay<=2001	USPAT	2004/04/30 09:34
14	525	(((((poly\$1silicon or (poly\$1crystalline adj silicon)) same (mask or hard\$1mask)) and (resist or photo\$1resist or photo\$1sensitive)) and ((poly\$1silicon or (poly\$1crystalline adj silicon)) same (HF or hydro\$1fluoric or ammonium or "NH.sub.4 OH")))) and ((mask or hard\$1mask) with (SiO or (silicon adj oxide) or (silicon adj dioxide) or SiO?sub.2))) and @ay<=2001	USPAT	2004/04/30 09:40
15	148	((((((poly\$1silicon or (poly\$1crystalline adj silicon)) same (mask or hard\$1mask)) and (resist or photo\$1resist or photo\$1sensitive)) and ((poly\$1silicon or (poly\$1crystalline adj silicon)) same (HF or hydro\$1fluoric or ammonium or "NH.sub.4 OH")))) and ((mask or hard\$1mask) with (SiO or (silicon adj oxide) or (silicon adj dioxide) or SiO?sub.2))) and @ay<=2001) and width (((((poly\$1silicon or (poly\$1crystalline adj silicon)) same (mask or hard\$1mask)) and (resist or photo\$1resist or photo\$1sensitive)) and ((poly\$1silicon or (poly\$1crystalline adj silicon)) same (HF or hydro\$1fluoric or ammonium or "NH.sub.4 OH")))) and ((mask or hard\$1mask) with (SiO or (silicon adj oxide) or (silicon adj dioxide) or SiO?sub.2))) and @ay<=2001) and width) and ((trim or trimmed or trimming or narrow or narrowing or under\$1cut or under\$1cutting) same (poly\$1silicon or (poly\$1crystalline adj silicon)))	USPAT	2004/04/30 09:35
16	117	((((((poly\$1silicon or (poly\$1crystalline adj silicon)) same (mask or hard\$1mask)) and (resist or photo\$1resist or photo\$1sensitive)) and ((poly\$1silicon or (poly\$1crystalline adj silicon)) same (HF or hydro\$1fluoric or ammonium or "NH.sub.4 OH")))) and ((mask or hard\$1mask) with (SiO or (silicon adj oxide) or (silicon adj dioxide) or SiO?sub.2))) and @ay<=2001) and width) and ((trim or trimmed or trimming or narrow or narrowing or under\$1cut or under\$1cutting) same (poly\$1silicon or (poly\$1crystalline adj silicon))) not (((((poly\$1silicon or (poly\$1crystalline adj silicon)) same (mask or hard\$1mask)) and (isotropic\$4)) and ((trim or trimmed or trimming or narrow or narrowing or under\$1cut or under\$1cutting) same (poly\$1silicon or (poly\$1crystalline adj silicon)))) and ((HF or hydro\$1fluoric) with (poly\$1silicon or silicon)))	USPAT	2004/04/30 09:35

17	377	(((((poly\$1silicon or (poly\$1crystalline adj silicon)) same (mask or hard\$1mask)) and (resist or photo\$1resist or photo\$1sensitive)) and ((poly\$1silicon or (poly\$1crystalline adj silicon)) same (HF or hydro\$1fluoric or ammonium or "NH.sub.4 OH")) and ((mask or hard\$1mask) with (SiO or (silicon adj oxide) or (silicon adj dioxide) or SiO?sub.2))) and @ay<=2001) and width) not ((((((poly\$1silicon or (poly\$1crystalline adj silicon)) same (mask or hard\$1mask)) and (resist or photo\$1resist or photo\$1sensitive)) and ((poly\$1silicon or (poly\$1crystalline adj silicon)) same (HF or hydro\$1fluoric or ammonium or "NH.sub.4 OH")) and ((mask or hard\$1mask) with (SiO or (silicon adj oxide) or (silicon adj dioxide) or SiO?sub.2))) and @ay<=2001) and width) and ((trim or trimmed or trimming or narrow or narrowing or under\$1cut or under\$1cutting) same (poly\$1silicon or (poly\$1crystalline adj silicon))))	USPAT	2004/04/30 10:09
18	9	("5429070" "5472564" "5541127" "5856227" "5930594" "6004853" "6235638" "6261934" "6316166").PN.	USPAT	2004/04/30 09:46
19	21800	(poly\$1silicon or (poly\$1crystalline adj silicon)).ab. or (poly\$1silicon or (poly\$1crystalline adj silicon)).clm.	USPAT	2004/04/30 10:00
20	14649	((poly\$1silicon or (poly\$1crystalline adj silicon)).ab. or (poly\$1silicon or (poly\$1crystalline adj silicon)).clm.) and (mask or hard\$1mask)	USPAT	2004/04/30 10:00
21	9954	((((poly\$1silicon or (poly\$1crystalline adj silicon)).ab. or (poly\$1silicon or (poly\$1crystalline adj silicon)).clm.) and (mask or hard\$1mask)) and ((poly\$1silicon or (poly\$1crystalline adj silicon)) near3 (line or gate or electrode))	USPAT	2004/04/30 10:02
22	1000	((((poly\$1silicon or (poly\$1crystalline adj silicon)).ab. or (poly\$1silicon or (poly\$1crystalline adj silicon)).clm.) and (mask or hard\$1mask)) and ((poly\$1silicon or (poly\$1crystalline adj silicon)) near3 (line or gate or electrode))) and ((isotropic\$4 or HF or hydro\$1fluoric or peroxide) with (poly\$1silicon or (poly\$1crystalline adj silicon)))	USPAT	2004/04/30 10:03
23	967	(((((poly\$1silicon or (poly\$1crystalline adj silicon)).ab. or (poly\$1silicon or (poly\$1crystalline adj silicon)).clm.) and (mask or hard\$1mask)) and ((poly\$1silicon or (poly\$1crystalline adj silicon)) near3 (line or gate or electrode))) and ((isotropic\$4 or HF or hydro\$1fluoric or peroxide) with (poly\$1silicon or (poly\$1crystalline adj silicon)))) and @ay<=2001	USPAT	2004/04/30 10:05

24	27	(((((poly\$1silicon or (poly\$1crystalline adj silicon)).ab. or (poly\$1silicon or (poly\$1crystalline adj silicon)).clm.) and (mask or hard\$1mask)) and ((poly\$1silicon or (poly\$1crystalline adj silicon)) near3 (line or gate or electrode))) and ((isotropic\$4 or HF or hydro\$1fluoric or peroxide) with (poly\$1silicon or (poly\$1crystalline adj silicon)))) and @ay<=2001) and (ground\$1rule or (ground adj rule))	USPAT	2004/04/30 10:07
25	533	(((((poly\$1silicon or (poly\$1crystalline adj silicon)).ab. or (poly\$1silicon or (poly\$1crystalline adj silicon)).clm.) and (mask or hard\$1mask)) and ((poly\$1silicon or (poly\$1crystalline adj silicon)) near3 (line or gate or electrode))) and ((isotropic\$4 or HF or hydro\$1fluoric or peroxide) with (poly\$1silicon or (poly\$1crystalline adj silicon)))) and @ay<=2001) and width	USPAT	2004/04/30 10:07
26	470	(((((poly\$1silicon or (poly\$1crystalline adj silicon)).ab. or (poly\$1silicon or (poly\$1crystalline adj silicon)).clm.) and (mask or hard\$1mask)) and ((poly\$1silicon or (poly\$1crystalline adj silicon)) near3 (line or gate or electrode))) and ((isotropic\$4 or HF or hydro\$1fluoric or peroxide) with (poly\$1silicon or (poly\$1crystalline adj silicon)))) and @ay<=2001) and width) and (resist! or photo\$1resist or photo\$1sensitive)	USPAT	2004/04/30 10:08

27	388	<pre> (((((poly\$1silicon or (poly\$1crystalline adj silicon)).ab. or (poly\$1silicon or (poly\$1crystalline adj silicon)).clm.) and (mask or hard\$1mask)) and ((poly\$1silicon or (poly\$1crystalline adj silicon)) near3 (line or gate or electrode))) and ((isotropic\$4 or HF or hydro\$1fluoric or peroxide) with (poly\$1silicon or (poly\$1crystalline adj silicon))) and (@ay<=2001) and width) and (resist! or photo\$1resist or photo\$1sensitive)) not (((((poly\$1silicon or (poly\$1crystalline adj silicon) same (mask or hard\$1mask)) and (isotropic\$4)) and ((trim or trimmed or trimming or narrow or narrowing or under\$1cut or under\$1cutting) same (poly\$1silicon or (poly\$1crystalline adj silicon))) and ((HF or hydro\$1fluoric) with (poly\$1silicon or silicon))) or ((((((poly\$1silicon or (poly\$1crystalline adj silicon)) same (mask or hard\$1mask)) and (resist or photo\$1resist or photo\$1sensitive)) and ((poly\$1silicon or (poly\$1crystalline adj silicon)) same (HF or hydro\$1fluoric or ammonium or "NH.sub.4 OH")) and ((mask or hard\$1mask) with (SiO or (silicon adj oxide) or (silicon adj dioxide) or SiO?sub.2)) and (@ay<=2001) and width) and ((trim or trimmed or trimming or narrow or narrowing or under\$1cut or under\$1cutting) same (poly\$1silicon or, (poly\$1crystalline adj silicon)))) or ((((((poly\$1silicon or (poly\$1crystalline adj silicon)).ab. or (poly\$1silicon or (poly\$1crystalline adj silicon)).clm.) and (mask or hard\$1mask)) and ((poly\$1silicon or (poly\$1crystalline adj silicon)) near3 (line or gate or electrode))) and ((isotropic\$4 or HF or hydro\$1fluoric or peroxide) with (poly\$1silicon or (poly\$1crystalline adj silicon))) and (@ay<=2001) and (ground\$1rule or (ground adj rule))))</pre>	USPAT	2004/04/30 10:08
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30	7	("4818334" "5030590" "5147499" "5228950" "5792708" "5976769" "6001688").PN.	USPAT	2004/04/30 10:12
31	12	("5286665" "5864160" "5990532" "6087208" "6110790" "6114228" "6180499" "6190981" "6194748" "6207485" "6306715" "6399469" "2001/0026982" "2002/0005581" "2002/0122995").PN. (poly\$1silicon or (poly\$1crystalline adj silicon) same (mask or hard\$1mask)) and T\$1shape\$1	USPAT	2004/04/30 10:16
32	277		USPAT	2004/04/30 10:52

33	269	((poly\$1silicon or (poly\$1crystalline adj silicon)) same (mask or hard\$1mask)) and T\$1shape\$1) not (((((((poly\$1silicon or (poly\$1crystalline adj silicon)).ab. or (poly\$1silicon or (poly\$1crystalline adj silicon)).clm.) and (mask or hard\$1mask)) and ((poly\$1silicon or (poly\$1crystalline adj silicon)) near3 (line or gate or electrode))) and ((isotropic\$4 or HF or hydro\$1fluoric or peroxide) with (poly\$1silicon or (poly\$1crystalline adj silicon)))) and @ay<=2001) and width) and (resist! or photo\$1resist or photo\$1sensitive)) not (((((poly\$1silicon or (poly\$1crystalline adj silicon)) same (mask or hard\$1mask)) and (isotropic\$4)) and ((trim or trimmed or trimming or narrow or narrowing or under\$1cut or under\$1cutting) same (poly\$1silicon or (poly\$1crystalline adj silicon)))) and ((HF or hydro\$1fluoric) with (poly\$1silicon or silicon))) or (((((poly\$1silicon or (poly\$1crystalline adj silicon)) same (mask or hard\$1mask)) and (resist or photo\$1resist or photo\$1sensitive)) and ((poly\$1silicon or (poly\$1crystalline adj silicon)) same (HF or hydro\$1fluoric or ammonium or "NH.sub.4 OH")) and ((mask or hard\$1mask) with (SiO or (silicon adj oxide) or (silicon adj dioxide) or SiO?sub.2))) and @ay<=2001) and width) and ((trim or trimmed or trimming or narrow or narrowing or under\$1cut or under\$1cutting) same (poly\$1silicon or (poly\$1crystalline adj silicon)))) or (((((poly\$1silicon or (poly\$1crystalline adj silicon)).ab. or (poly\$1silicon or (poly\$1crystalline adj silicon)).clm.) and (mask or hard\$1mask)) and ((poly\$1silicon or (poly\$1crystalline adj silicon)) near3 (line or gate or electrode))) and ((isotropic\$4 or HF or hydro\$1fluoric or peroxide) with (poly\$1silicon or (poly\$1crystalline adj silicon)))) and @ay<=2001) and (ground\$1rule or (ground adj rule)))) not (((((poly\$1silicon or (poly\$1crystalline adj silicon)) same (mask or hard\$1mask)) and (resist or photo\$1resist or photo\$1sensitive)) and ((poly\$1silicon or (poly\$1crystalline adj silicon)) same (HF or hydro\$1fluoric or ammonium or "NH.sub.4 OH")) and ((mask or hard\$1mask) with (SiO or (silicon adj oxide) or (silicon adj dioxide) or SiO?sub.2))) and @ay<=2001) and width) not (((((poly\$1silicon or (poly\$1crystalline adj silicon)) same (mask or hard\$1mask)) and (resist or photo\$1resist or photo\$1sensitive)) and ((poly\$1silicon or (poly\$1crystalline adj silicon)) same (HF or hydro\$1fluoric or ammonium or "NH.sub.4 OH")) and ((mask or hard\$1mask) with (SiO or (silicon adj oxide) or (silicon adj dioxide) or SiO?sub.2))) and @ay<=2001) and width) and ((trim or trimmed or trimming or narrow or narrowing or under\$1cut or under\$1cutting) same (poly\$1silicon or (poly\$1crystalline adj silicon))))))	USPAT	2004/04/30 10:53
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34	258	<p>(((((poly\$1silicon or (poly\$1crystalline adj silicon)) same (mask or hard\$1mask)) and T\$1shape\$1) not (((((((poly\$1silicon or (poly\$1crystalline adj silicon)).ab. or (poly\$1silicon or (poly\$1crystalline adj silicon)).clm.) and (mask or hard\$1mask)) and ((poly\$1silicon or (poly\$1crystalline adj silicon)) near3 (line or gate or electrode))) and ((isotropic\$4 or HF or hydro\$1fluoric or peroxide) with (poly\$1silicon or (poly\$1crystalline adj silicon))) and @ay<=2001) and width) and (resist! or photo\$1resist or photo\$1sensitive)) not ((((((poly\$1silicon or (poly\$1crystalline adj silicon)) same (mask or hard\$1mask)) and (isotropic\$4)) and ((trim or trimmed or trimming or narrow or narrowing or under\$1cut or under\$1cutting) same (poly\$1silicon or (poly\$1crystalline adj silicon))) and ((HF or hydro\$1fluoric) with (poly\$1silicon or silicon))) or ((((((poly\$1silicon or (poly\$1crystalline adj silicon)) same (mask or hard\$1mask)) and (resist or photo\$1resist or photo\$1sensitive)) and ((poly\$1silicon or (poly\$1crystalline adj silicon)) same (HF or hydro\$1fluoric or ammonium or "NH.sub.4 OH")) and ((mask or hard\$1mask) with (SiO or (silicon adj oxide) or (silicon adj dioxide) or SiO?sub.2)) and @ay<=2001) and width) and ((trim or trimmed or trimming or narrow or narrowing or under\$1cut or under\$1cutting) same (poly\$1silicon or (poly\$1crystalline adj silicon))) or ((((((poly\$1silicon or (poly\$1crystalline adj silicon)).ab. or (poly\$1silicon or (poly\$1crystalline adj silicon)).clm.) and (mask or hard\$1mask)) and ((poly\$1silicon or (poly\$1crystalline adj silicon)) near3 (line or gate or electrode))) and ((isotropic\$4 or HF or hydro\$1fluoric or peroxide) with (poly\$1silicon or (poly\$1crystalline adj silicon))) and @ay<=2001) and (ground\$1rule or (ground adj rule)))) not ((((((poly\$1silicon or (poly\$1crystalline adj silicon)) same (mask or hard\$1mask)) and (resist or photo\$1resist or photo\$1sensitive)) and ((poly\$1silicon or (poly\$1crystalline adj silicon)) same (HF or hydro\$1fluoric or ammonium or "NH.sub.4 OH")) and ((mask or hard\$1mask) with (SiO or (silicon adj oxide) or (silicon adj dioxide) or SiO?sub.2)) and @ay<=2001) and width) not ((((((poly\$1silicon or (poly\$1crystalline adj silicon)) same (mask or hard\$1mask)) and (resist or photo\$1resist or photo\$1sensitive)) and ((poly\$1silicon or (poly\$1crystalline adj silicon)) same (HF or hydro\$1fluoric or ammonium or "NH.sub.4 OH")) and ((mask or hard\$1mask) with (SiO or (silicon adj oxide) or (silicon adj dioxide) or SiO?sub.2)) and @ay<=2001) and width) and ((trim or trimmed or trimming or narrow or narrowing or under\$1cut or under\$1cutting) same (poly\$1silicon or (poly\$1crystalline adj silicon))))))) and @ay<=2001</p>	USPAT	2004/04/30 10:53
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35	5	("4795718" "5001077" "5147814" "5286652" "5650342").PN.	USPAT	2004/04/30 11:19
36	0	sub\$1minium adj ground\$1rule	USPAT	2004/04/30 12:04
37	0	minium adj ground\$1rule	USPAT	2004/04/30 12:04
38	0	sub\$1minimum adj ground\$1rule	USPAT	2004/04/30 12:04
39	15	minimum adj ground\$1rule	USPAT	2004/04/30 12:14
40	25	minimum adj ground adj rule	USPAT	2004/04/30 12:14
41	21	(minimum adj ground adj rule) not (minimum adj ground\$1rule)	USPAT	2004/04/30 12:24
42	1	6013570.pn.	USPAT	2004/04/30 12:25
43	235	(poly\$1silicon or (poly\$1crystalline adj silicon)) with (hydro\$1fluoric or HF) with (nitric or HNO?sub.3)	USPAT	2004/04/30 12:39
44	19	(poly\$1silicon or (poly\$1crystalline adj silicon)) with (hydro\$1fluoric or HF) with (nitric or HNO?sub.3) with (phosphoric or "H.sub.3 PO.sub.4")	USPAT	2004/04/30 12:44
45	1542	(poly\$1silicon or (poly\$1crystalline adj silicon)) with (hydro\$1fluoric or HF)	USPAT	2004/04/30 13:25
46	20	((poly\$1silicon or (poly\$1crystalline adj silicon)) with (hydro\$1fluoric or HF)) same (ozone or O?sub.3 or ozonated or ozonating)	USPAT	2004/04/30 12:45
47	13892	(mask or hard\$1mask) with ((silicon adj oxide) or (silicon adj dioxide) or SiO or SiO?sub.2)	USPAT	2004/04/30 13:20
48	91	(mask or hard\$1mask) with ((silicon adj oxide) or (silicon adj dioxide) or SiO or SiO?sub.2) with (SiON or oxytride)	USPAT	2004/04/30 13:21
49	13	((mask or hard\$1mask) with ((silicon adj oxide) or (silicon adj. dioxide) or SiO or SiO?sub.2) with (SiON or oxytride)) same (ARC or anti\$1reflective or BARC)	USPAT	2004/04/30 13:22
50	440	(poly\$1silicon or (poly\$1crystalline adj silicon)) with (ozone or O?sub.3 or ozonated or ozonating)	USPAT	2004/04/30 13:29
51	14	((poly\$1silicon or (poly\$1crystalline adj silicon)) with (ozone or O?sub.3 or ozonated or ozonating)) same (HF or hydro\$1fluoric)	USPAT	2004/04/30 13:26
52	49	(poly\$1silicon or (poly\$1crystalline adj silicon)) with (peroxide or "H.sub.2 O.sub.2") with ((ammonium adj hydroxide) or "NH.sub.4 OH")	USPAT	2004/04/30 15:30
53	1	Grant-Casey-J.in.	USPAT	2004/04/30 15:30
54	4	Grant-Casey-J.in.	USPAT; US-PGPUB; EPO; JPO; DERWENT; IBM TDB	2004/04/30 15:30
55	41	Leidy-Robert-K.in.	USPAT; US-PGPUB; EPO; JPO; DERWENT; IBM TDB	2004/04/30 15:30
56	7	Sharrows-Joel-M.in.	USPAT; US-PGPUB; EPO; JPO; DERWENT; IBM TDB	2004/04/30 15:30
57	4	(("6107172") or ("5965461") or ("5431770") or ("5139904")).PN.	USPAT	2004/04/30 15:31